



LAW OFFICES
CHRISTOPHER P. MAIORANA, P.C.
24025 GREATER MACK, SUITE 200
ST. CLAIR SHORES, MICHIGAN 48080

CHRISTOPHER P. MAIORANA
ROBERT M. MILLER
THOMAS W. SAUR

(810) 498-0670
Fax (810) 498-0673

PATENTS, TRADEMARKS
& COPYRIGHTS

June 6, 2000

VIA E-MAIL

Paul Cheng
Kuang-Yu Chen
Frank Hwang
Eric Chen
Hyunbae Kim
Cypress Semiconductor Corp.
101 Nicholson Lane
San Jose, CA 95134-1359

Re: United States Patent Application Entitled:
METHOD AND APPARATUS FOR OVERCLOCKING RECOVERY IN A
PLL
Your Reference No.: CD00060
Our Reference No.: 0325.00370

Dear Paul, Kuang-Yu, Frank, Eric and Hyunbae:

Enclosed is a first draft of a patent application directed to the above-referenced invention. The patent application is based upon technical information found in the invention disclosure you provided.

In reviewing the application, please be sure to consider the following:

1. The application should provide sufficient information to teach one of ordinary skill in the art how to make and use the invention. As a minimum threshold, consider if you were reading the disclosure for the first time without your previous knowledge of the application. You should be able to make and use the invention without undue experimentation. While some experimentation may be required, if undue experimentation would be needed to practice the invention, not enough information is provided in the application. Please call me if you have any questions regarding this standard.
2. The application should be technically accurate.

Paul Cheng
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3. The closest references that I am aware of will be cited with the application. If you are aware of other references, either articles or patents, which disclose pertinent information not mentioned in the application or disclosure, please advise me and provide me with a copy of such materials.
4. If Cypress proprietary terms are used, please point them out to me.
5. The patent application should disclose the best mode of carrying out the invention. In other words, if you are aware of a better way of practicing the invention that is not included in the draft, please let me know.

Please appreciate that this is the first draft of the patent application for the above-referenced invention. It is expected that this draft may be modified based upon your input. With this in mind, please make whatever additions, deletions, corrections or comments you desire right on the enclosed copy of the draft and send or fax the corrected draft to me. If you have questions regarding the review of this draft, or feel it would save you time in review, please feel free to call me for a discussion. Your prompt attention to this matter will be appreciated.

Very truly yours,

CHRISTOPHER P. MAIORANA, P.C.

Christopher P. Maiorana

CPM/mdb
Enclosure

cc: Laura Engurasoff, Esq. (via fax w/enclosure)